



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Hytros, et al.

Serial No.: 10/033,544

Confirmation No.: 7363

Filed: December 27, 2001

**For: Dual-Gas Delivery System
for Chemical Vapor
Deposition Processes**

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Group Art Unit:

Examiner: to be assigned

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

CERTIFICATE OF MAILING
37 CFR 1.8

I hereby certify that this correspondence is being deposited on
April 18, 2002 with the United States Postal Service as First
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4/18/02 B. Jodi Patterson
Date Signature

INFORMATION DISCLOSURE STATEMENT

The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

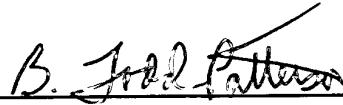
While the information submitted in this Information Disclosure Statement may be material pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication, or other information referred to therein is prior art for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97, this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possibly material information as defined under 37 CFR § 1.56(a) exists.

The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

Applicant believes that no fee is due as a result of this filing. However, If the Commissioner deems that fees are due under 37 CFR § 1.17(p) pursuant to § 1.97, he is hereby authorized to charge this fee, and any other fee necessary to make this submission timely, to Deposit Account No. 20-0782/AMAT 6551/CMI/TICL/RKK.

Respectfully submitted,

A handwritten signature in black ink, appearing to read "B. Todd Patterson", is written over a horizontal line.

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U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/6551/CMI/TICL/ RKK	Serial No. 10/033,544
INFORMATION DISCLOSURE STATEMENT BY APPLICATION		Applicant Hytros, et al.	Confirmation No.: 7363
(Use several sheets if necessary)		Filing Date December 27, 2001	Group Unknown
Examiner:			

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1	6,200,844	03/13/2001	Huang	438	238	02/12/1999
	A2	6,148,761	11/21/2000	Majewski et al.	118	715	12/09/1998
	A3	6,086,677	07/11/2000	Umotoy et al.	118	715	06/16/1998
	A4	5,970,378	10/19/1999	Shue et al.	438	656	07/23/1997
	A5	5,956,595	09/21/1999	Zenke	438	398	07/15/1997
	A6	5,871,586	02/16/1999	Crawley et al.	118	715	04/09/1997
	A7	5,665,640	09/09/1997	Foster et al.	438	680	06/03/1994
	A8	5,576,071	11/19/1996	Sandhu	427	534	11/08/1994
	A9	5,567,483	10/22/1996	Foster et al.	427	535	06/05/1995
	A10	5,308,655	05/03/1994	Eichman et al.	427	248.1	02/10/1992
	A11	5,279,857	01/18/1994	Eichman et al.	427	255	08/16/1991

F reign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1	63-22984	09/26/1988	JP	H01L	12/28	<input type="checkbox"/>	<input type="checkbox"/>
	B2	0711846	05/15/1996	EP	C23C	16/34	<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
	C1	Arena, et al., "A New Low Temperature PECVD TiN Compatible With Multilevel Vias Application", VMIC Conference, pp. 566-71, June 18-20, 1996
	C2	Allendorf, et al., "Chemical Vapor Deposition", Proceedings of the Fourteenth International Conference and EUROCV D-11, Vol. 97-25, pp. 1625-33.
	C3	Konecni, et al., "A Stable Plasma Treated CVD Titanium Nitride Film for Barrier/Glue Layer Applications", VMIC Conference, pp. 181-3.
	C4	Kim, et al., "Effect of N ₂ /H _x Plasma Treatment on the Properties of TiN Films Prepared by Chemical Vapor Deposition from TiCl ₄ and NH ₃ ", Jap. J. Appl. Phys., Vol. 38, Part 2, No. 4B, pp. L461-3, April 15, 1999
	C5	USSN 09/978,140, Zhang, et al., "Method of Titanium and Titanium Nitride Layer Deposition, filed October 15, 2001

Examiner

Date Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.